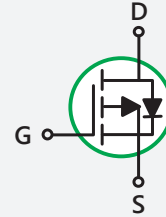
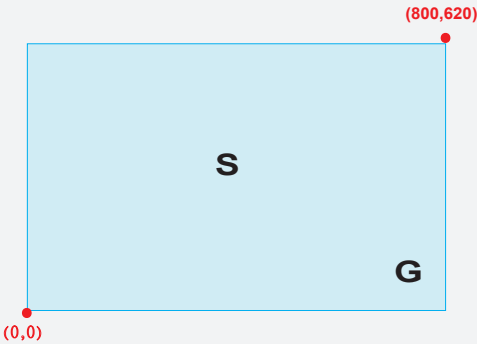


FEATURES

- P-Channel, -60V
- $R_{ds}(ON) = 182m\Omega$ (Typ.) @ $V_{GS} = -10V$
- Exceptional on-resistance and maximum DC current capability
high density cell design for extremely low $R_{DS}(ON)$



| Bonding Pad Information | Chip Information | |
|--|--------------------------------|-----------------------|
|  | Wafer Name | DC6M060P182M7 |
| | Wafer Diameter | 6 inches |
| | Wafer Thickness | 7 mils |
| | Front-side Metallization | Al/Si/Cu (4um) |
| | Back-side Metallization | Ti/Ni/Ag |
| | Bonding Type | Gate: 1.5mil Cu x 1 |
| | | Source: 1.5mil Cu x 5 |
| | Die Size (without scribe line) | 800um x 620um |
| | Scribe Line Width | 60um |
| | Gate Pad Size | 150um x 150um |
| Gross Die | 27K ea | |

ABSOLUTE MAXIMUM RATINGS ($T_c = 25^\circ C$ unless otherwise noted)

| Parameter | Symbol | Limit | Units |
|--|----------------|------------|------------|
| Drain-Source Voltage | V_{DS} | -60 | V |
| Gate-Source Voltage | V_{GS} | ± 20 | V |
| Operating Junction and Storage Temperature Range | T_J, T_{STG} | -55 to 150 | $^\circ C$ |

ELECTRICAL CHARACTERISTICS ($T_c = 25^\circ C$ unless otherwise noted)

| Parameter | Symbol | Test Conditions | Min | Typ | Max | Units |
|----------------------------------|--------------|------------------------------------|------|------|-----------|---------|
| Drain-Source Breakdown Voltage | BV_{DSS} | $V_{GS} = 0V, I_D = -250\mu A$ | -60 | | | V |
| Zero Gate Voltage Drain Current | I_{DSS} | $V_{DS} = -48V, V_{GS} = 0V$ | | | -1 | μA |
| Gate-Body Leakage Current | I_{GSS} | $V_{GS} = \pm 20V, V_{DS} = 0V$ | | | ± 100 | nA |
| Gate Threshold Voltage | $V_{GS(th)}$ | $V_{DS} = V_{GS}, I_D = -250\mu A$ | -1.0 | -1.5 | -2.0 | V |
| Drain-Source On-State Resistance | $R_{DS(ON)}$ | $V_{GS} = -10V, I_D = -1A$ | | 182 | 218 | m ohm |
| | | $V_{GS} = -4.5V, I_D = -0.5A$ | | 228 | 285 | m ohm |

Notes:

1. Pulse Test: Pulse Width $\leq 300\mu s$, Duty Cycle $\leq 2\%$.
2. $R_{DS}(ON)$ calculated by SOP-8 Package Type.